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Tech ID: 21808

ADDITIONAL TECHNOLOGIES BY THESE INVENTORS

- ► Vertical Cavity Surface-Emitting Lasers with Continuous Wave Operation
- ▶ Eliminating Misfit Dislocations with In-Situ Compliant Substrate Formation
- ► Aluminum-cladding-free Nonpolar III-Nitride LEDs and LDs
- Low-Cost Zinc Oxide for High-Power-Output, GaN-Based LEDs (UC Case 2010-183)
- Defect Reduction in GaN films using in-situ SiNx Nanomask
- ► Enhanced Light Extraction LED with a Tunnel Junction Contact Wafer Bonded to a Conductive Oxide
- ► Low Temperature Deposition of Magnesium Doped Nitride Films
- ► Transparent Mirrorless (TML) LEDs
- ▶ Optimization of Laser Bar Orientation for Nonpolar Laser Diodes
- ▶ Stand-Alone Ceramic Phosphor Composites for Laser-Excited Solid-State White Lighting
- ▶ Method for Enhancing Growth of Semipolar Nitride Devices
- ▶ Ultraviolet Laser Diode on Nano-Porous AlGaN template
- ▶ Improved Reliability & Enhanced Performance of III-Nitride Tunnel Junction Optoelectronic Devices
- Improved Fabrication of Nonpolar InGaN Thin Films, Heterostructures, and Devices
- ► Growth of High-Quality, Thick, Non-Polar M-Plane GaN Films
- ► High-Efficiency, Mirrorless Non-Polar and Semi-Polar Light Emitting Devices
- Oxyfluoride Phosphors for Use in White Light LEDs
- ▶ Technique for the Nitride Growth of Semipolar Thin Films, Heterostructures, and Semiconductor Devices
- (In,Ga,AI)N Optoelectronic Devices with Thicker Active Layers for Improved Performance
- ► Thermally Stable, Laser-Driven White Lighting Device
- ▶ MOCVD Growth of Planar Non-Polar M-Plane Gallium Nitride
- ▶ Methods for Fabricating III-Nitride Tunnel Junction Devices
- ▶ Low-Droop LED Structure on GaN Semi-polar Substrates
- ► Contact Architectures for Tunnel Junction Devices
- ▶ Semi-polar LED/LD Devices on Relaxed Template with Misfit Dislocation at Hetero-interface
- ▶ Semipolar-Based Yellow, Green, Blue LEDs with Improved Performance
- ▶ III-Nitride-Based Devices Grown On Thin Template On Thermally Decomposed Material
- ► Growth of Semipolar III-V Nitride Films with Lower Defect Density
- ▶ III-Nitride Tunnel Junction LED with High Wall Plug Efficiency
- ▶ Tunable White Light Based on Polarization-Sensitive LEDs

- ► Cleaved Facet Edge-Emitting Laser Diodes Grown on Semipolar GaN
- ► Growth of High-Performance M-plane GaN Optical Devices
- ▶ Packaging Technique for the Fabrication of Polarized Light Emitting Diodes
- ► Improved Anisotropic Strain Control in Semipolar Nitride Devices
- ► III-V Nitride Device Structures on Patterned Substrates
- ► Method for Increasing GaN Substrate Area in Nitride Devices
- ▶ High-Intensity Solid State White Laser Diode
- ▶ Nitride Based Ultraviolet LED with an Ultraviolet Transparent Contact
- ► GaN-Based Thermoelectric Device for Micro-Power Generation
- ▶ Limiting Strain-Relaxation in III-Nitride Heterostructures by Substrate Patterning
- ► LED Device Structures with Minimized Light Re-Absorption
- ► Growth of Planar Semi-Polar Gallium Nitride
- ▶ UV Optoelectronic Devices Based on Nonpolar and Semi-polar AllnN and AllnGaN Alloys
- ▶ Defect Reduction of Non-Polar and Semi-Polar III-Nitrides
- ► Enhancing Growth of Semipolar (Al,In,Ga,B)N Films via MOCVD

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